

# Wireless Interconnection on Si LSI using Integrated Antenna

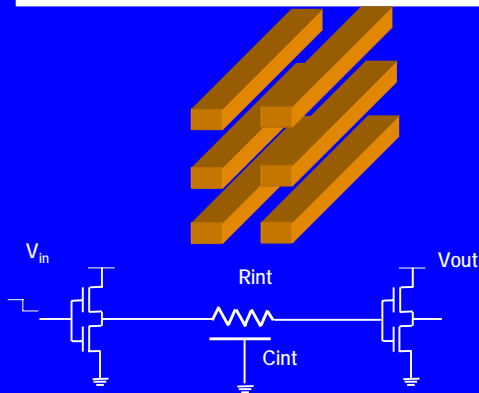
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# Outline

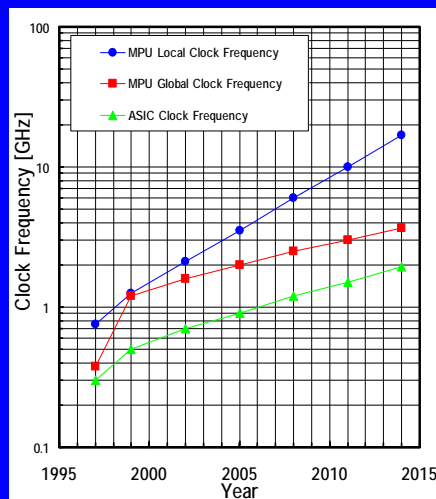
1. Introduction
2. Concept of Wireless Interconnects
3. Experimental Setup and Antenna Configuration
4. Transmission Characteristics of Integrated Antenna
5. Conclusion

# Limitation of Clock Frequency for ULSI

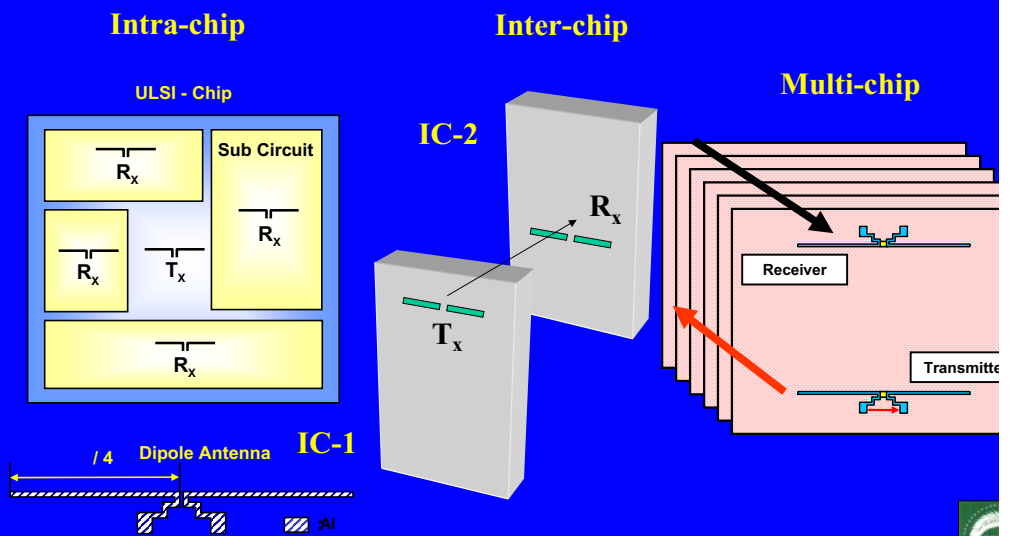


$$T_{90\%} = 1.0R_{int}C_{int} + 2.3(R_rC_{int} + R_rC_L + R_{int}C_L) \approx 2.3(R_r + R_{int})C_{int} \quad (C_L \ll C_{int})$$

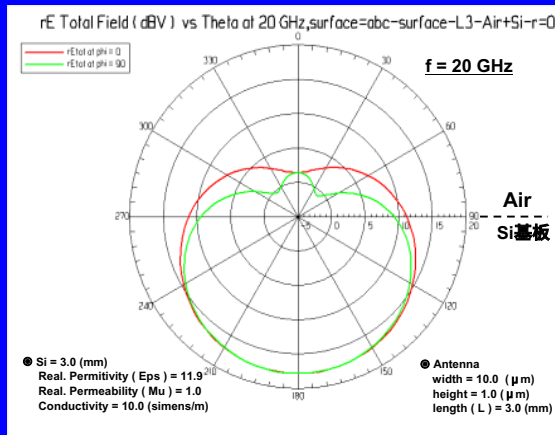
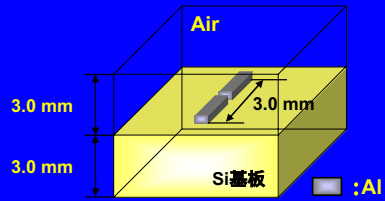
$$T_{90\%} \approx 2.3(R_r + R_{int})C_{int} = 2.3(178 + 2400) \times 3.54 \times 10^{-15} = 2.1nsec$$



# Wireless Clock and Data Transmission for Si ULSIs



# Transmission through Si using Integrated Antenna



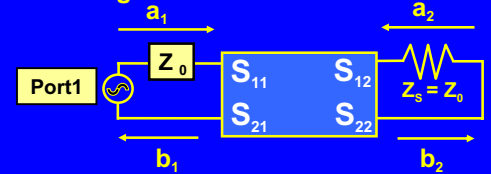
Radiation Pattern of Si Integrated Antenna

$$\lambda_{Air} = \frac{v_{\epsilon}}{f} = \frac{3.0 \times 10^8}{20 \times 10^9} = 1.5 \text{ (cm)}$$

$$\lambda_{Si} = \frac{\lambda_{Air}}{\sqrt{\epsilon_{Si}}} = \frac{1.5 \text{ (cm)}}{\sqrt{12}} = 4.33 \text{ (mm)}$$

# Measurement Setup for Transmission Gain

## Scattering – Parameter



$$\begin{bmatrix} b_1 \\ b_2 \end{bmatrix} = \begin{bmatrix} S_{11} & S_{12} \\ S_{21} & S_{22} \end{bmatrix} \begin{bmatrix} a_1 \\ a_2 \end{bmatrix}$$

$a_i$  - Incident wave  
 $b_j$  - Reflected wave

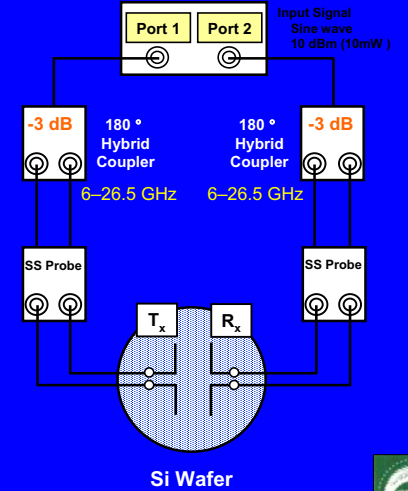
$$S_{ii} = \frac{b_i}{a_i} \Big|_{a_j = 0} \quad S_{ij} = \frac{b_j}{a_i} \Big|_{a_j = 0}$$

## Antenna transmission gain ( $G_a$ )

$$G_a = G_r \cdot G_t \cdot \left( \frac{\lambda}{4\pi R} \right)^2 = \frac{|S_{21}|^2}{(1 - |S_{11}|^2)(1 - |S_{22}|^2)}$$

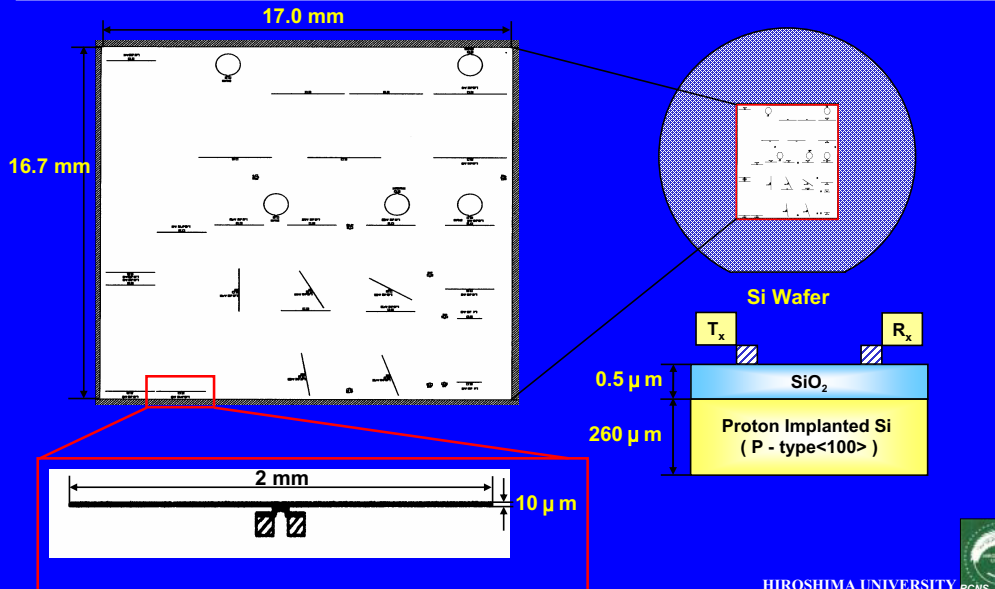
$G_r$  = Receiver Gain,  $G_t$  = Transmitter Gain

HP8510C Vector Network Analyzer

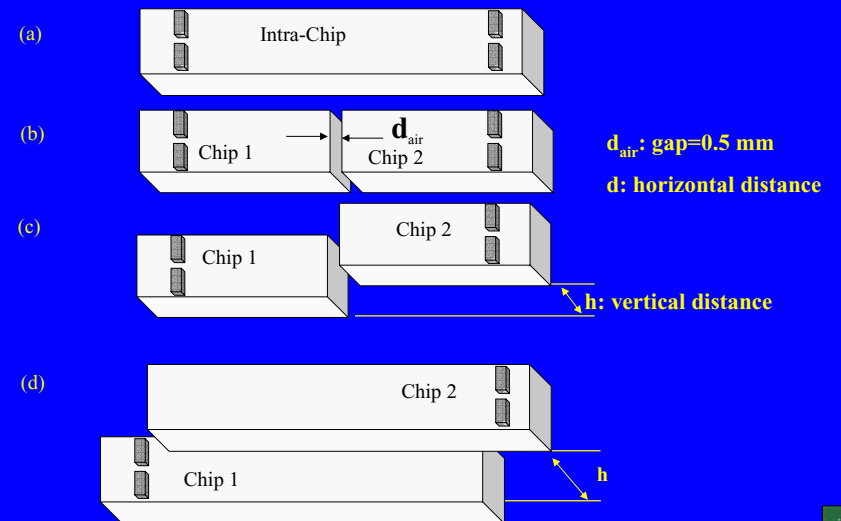


Si Wafer

# Layout of Integrated Antenna for Intra-chip Transmission



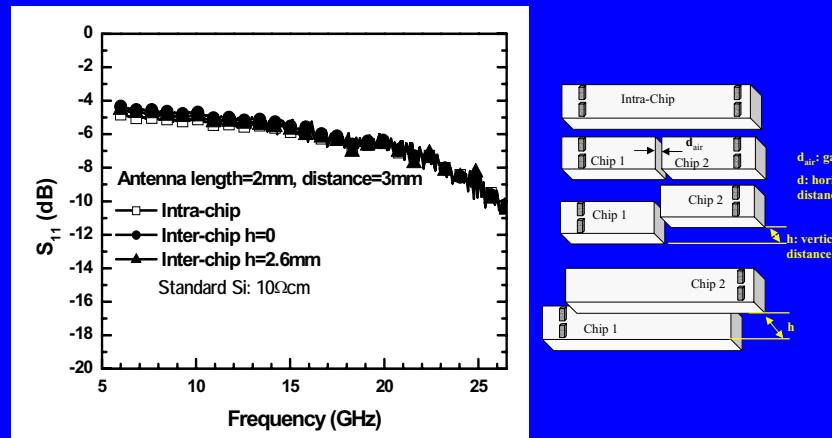
# Configuration of Integrated Antennas for Inter-chip Transmission



$d_{air}$ : gap=0.5 mm  
 $d$ : horizontal distance

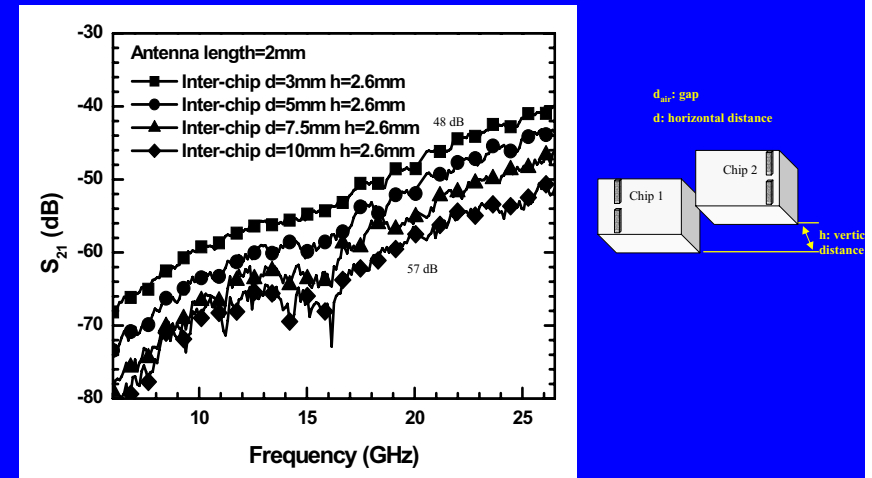
$h$ : vertical distance

## Reflection Coefficient ( $S_{11}$ ) of Transmitting Antennas on Si



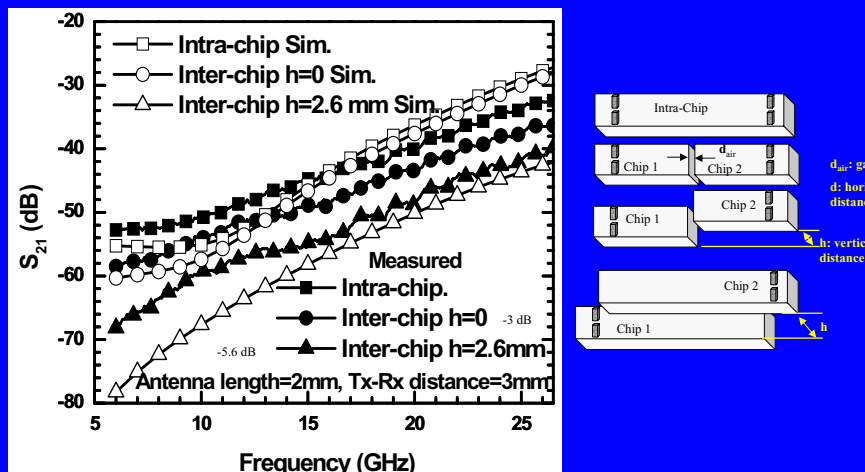
Reflection coefficients does not depend on the inter/intra-chip antenna configurations

## Inter-chip Transmission Coefficient versus Frequency Dependence of Horizontal Distance on Transmission Coefficient



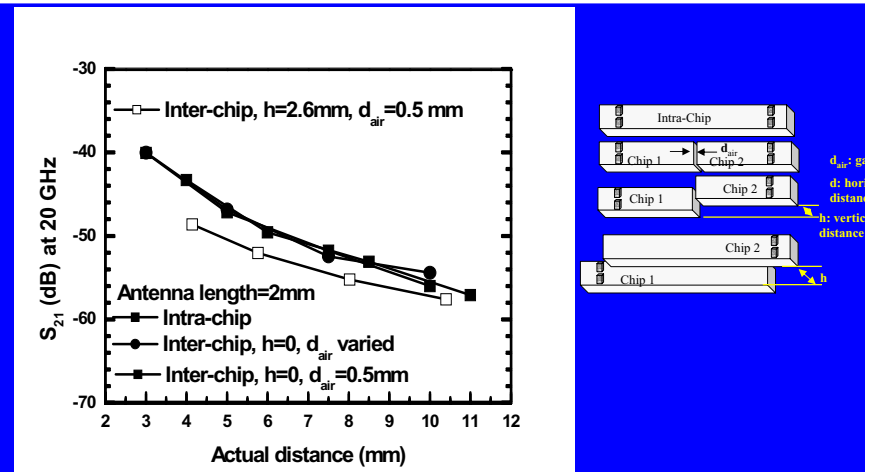
Transmission coefficients at 20 GHz are -48.7 and -57.9 dB at distances of 3 and 10 mm, respectively.

## Inter-chip Transmission Coefficient versus Frequency Dependence of Vertical Distance on Transmission Coefficient ( $S_{21}$ )



Inter-chip transmission coefficient decreases  
-3 dB by a horizontal gap of 0.5 mm and -5.6 dB by 2.6 mm vertical distance.

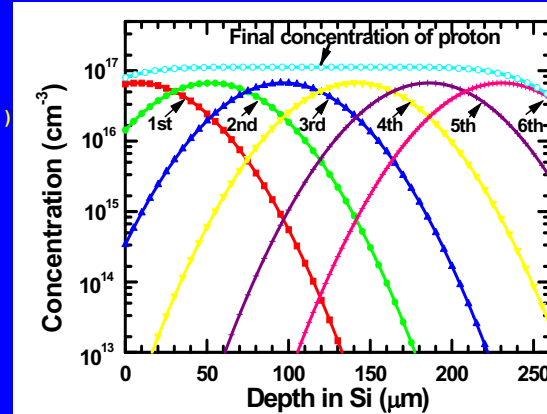
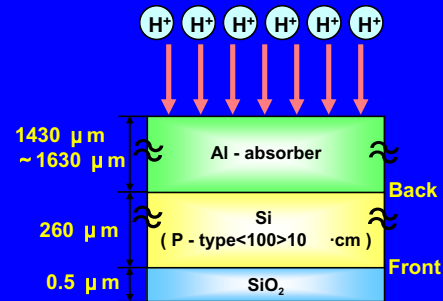
## Inter-Chip Transmission Coefficient versus Actual Distance



Transmission coefficients depends on effective distances between antennas  
The major path of EM wave is in the low-k substrate so that air gap has negligible effect.

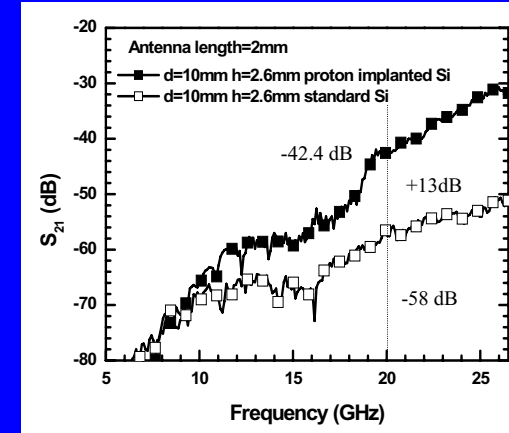
## Effect of High-Resistivity Si Substrate by Proton Implantation

Proton Energy : 17.4 MeV  
 Proton Dose :  $5 \times 10^{12} \sim 1 \times 10^{15} / \text{cm}^2$   
 No. of Implantation = 6  
 Range control : by varying Al  
 Al absorber thickness :  $1630 \mu\text{m} - n \times 40 \mu\text{m}$  ( $n = 0 \sim 5$ )  
 Si Resistivity :  $65 \text{ k} \cdot \text{cm}$  ( $5 \times 10^{14} / \text{cm}^2$ )



Proton Dose :  $5 \times 10^{14} / \text{cm}^2$

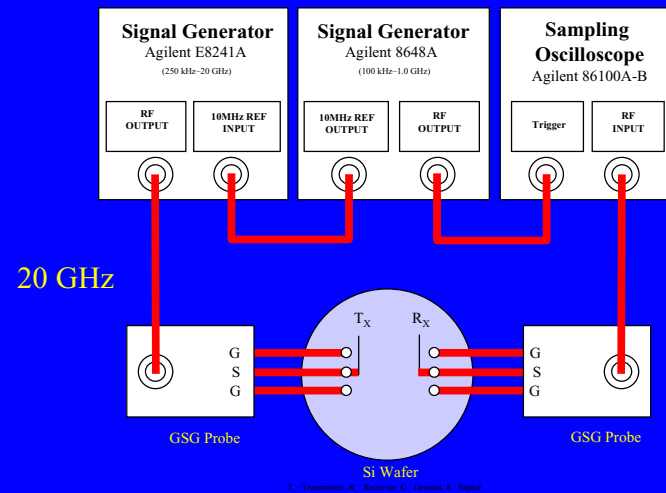
## Effect of High-Resistivity Substrate on Inter-Chip Transmission



Transmission coefficient of -57.9 dB at 20 GHz for horizontal separation distance of 10.5 mm and the vertical distance of 2.6 mm.

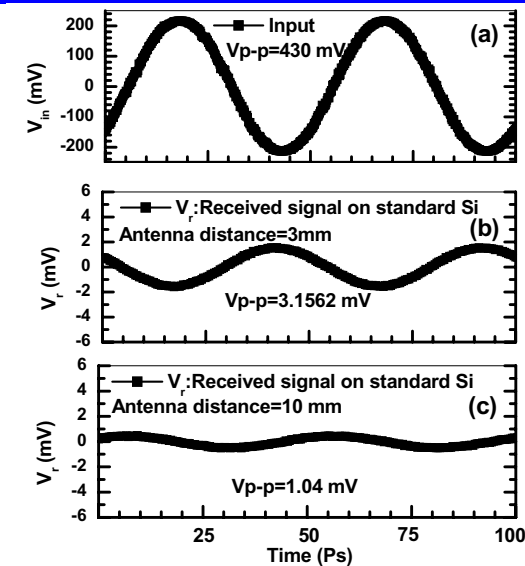
High resistivity Si substrate by proton implantation improved the transmission coefficient to -42.4 dB. The transmission coefficient on the proton implanted Si substrate increased 13.4 dB at 20 GHz

## Measurement for Time Domain Signal Transmission

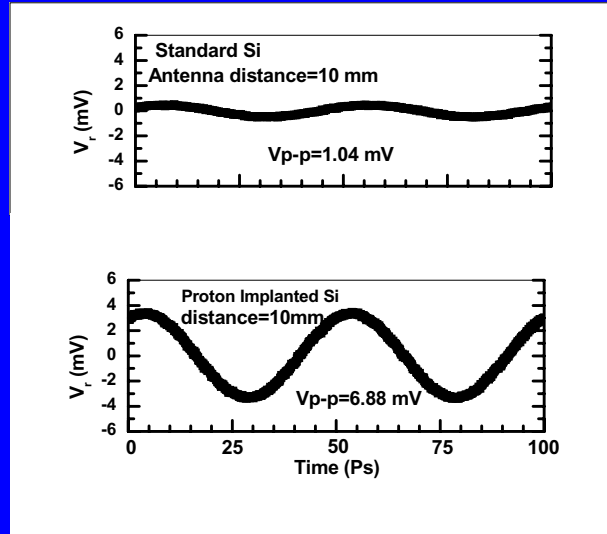


T: Transmitter, R: Receiver, G: Ground, S: Signal

## Inter-chip Transmission of Sinusoidal Signal at 20GHz on $10 \Omega\text{cm}$ Si



## Effect of High Resistivity Si on Inter-chip Transmission of Sinusoidal Signal



## Conclusion

Inter-chip signal transmission between Si substrates shows a transmission coefficient of -57.9 dB at 20 GHz for 2 mm long antenna when the transmitting and the receiving antenna separation distance is 10.5 mm and the receiver chip is at a height of 2.6 mm from the transmitter chip.

When high resistivity Si substrate is used the transmission coefficient increases 13.4 dB at 20 GHz and the amplitude of the received sinusoidal signal at 20 GHz increases from 1 mV to 6.8 mV.

This demonstrates the feasibility and the effectiveness of inter-chip wireless signal transmission using integrated antenna with high resistivity Si in 3-D ICs or in stacked chip scale packaging.